



U.S. Department of Commerce, Patent and Trademark	Atty. Docket No.	Application No.
INFORMATION DISCLOSURE STATEMENT BY APPLICANT	TNCR.189US0	09/741,663
(Use several sheets if necessary)	Applicant(s)	Conf. No.
	Andrei V. Shchegrov	7526
	Filing Date	Group
	December 19, 2000	2877

U.S. Patent Documents

*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate

Foreign Patent Documents

							Translation	
	Document	Date	Country	Class	Subclass		Yes	No

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

	1	Patent Search conducted on August 1, 2000
	2	"Ultraviolet-visible ellipsometry for process control during the etching of submicrometer features," N. Blayo et al., <i>J. Opt. Soc. Am. A</i> , Vol. 12, No. 3, March 1995, pp. 591-599.
	3	"Algorithm Implementation and Techniques for Providing More Reliable Overlay Measurements and Better Tracking of the Shallow Trench Isolation (STI) Process," D. Schramm et al., <i>SPIE: Conference on Metrology, Inspection, and Process Control of Microlithography XIII</i> , March 1999, pp. 116-122.

Examiner	Date Considered 27 AUGUST 2004
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.